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(12) **United States Design Patent**
Tanaka

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(54) **ION SHIELD PLATE FOR PLASMA PROCESSING DEVICE**

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Tokyo (JP)

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(51) **LOC (13) Cl.** **24-02**

(52) **U.S. Cl.**
USPC **D24/224**

(58) **Field of Classification Search**

USPC ... D24/107, 110.6, 113, 129, 144, 193, 197,
D24/168, 170, 187, 200, 205, 206, 224;
D23/200, 213-215, 222, 223, 229, 283;
D15/126, 140, 144.1; D8/352
CPC H01J 37/32082; H01J 37/32541; H01J
19/54; H01J 5/48; H01R 13/514; H01R
31/02; F21V 5/00

See application file for complete search history.

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(57) **CLAIM**

The ornamental design for an ion shield plate for plasma processing apparatus, as shown and described.

DESCRIPTION

FIG. 1 is a front, top, and right side perspective view of an ion shield plate for plasma processing apparatus according to the design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a top plan view thereof;

FIG. 4 is a bottom plan view thereof;

FIG. 5 is a right side elevational view thereof;

FIG. 6 is a left side elevational view thereof;

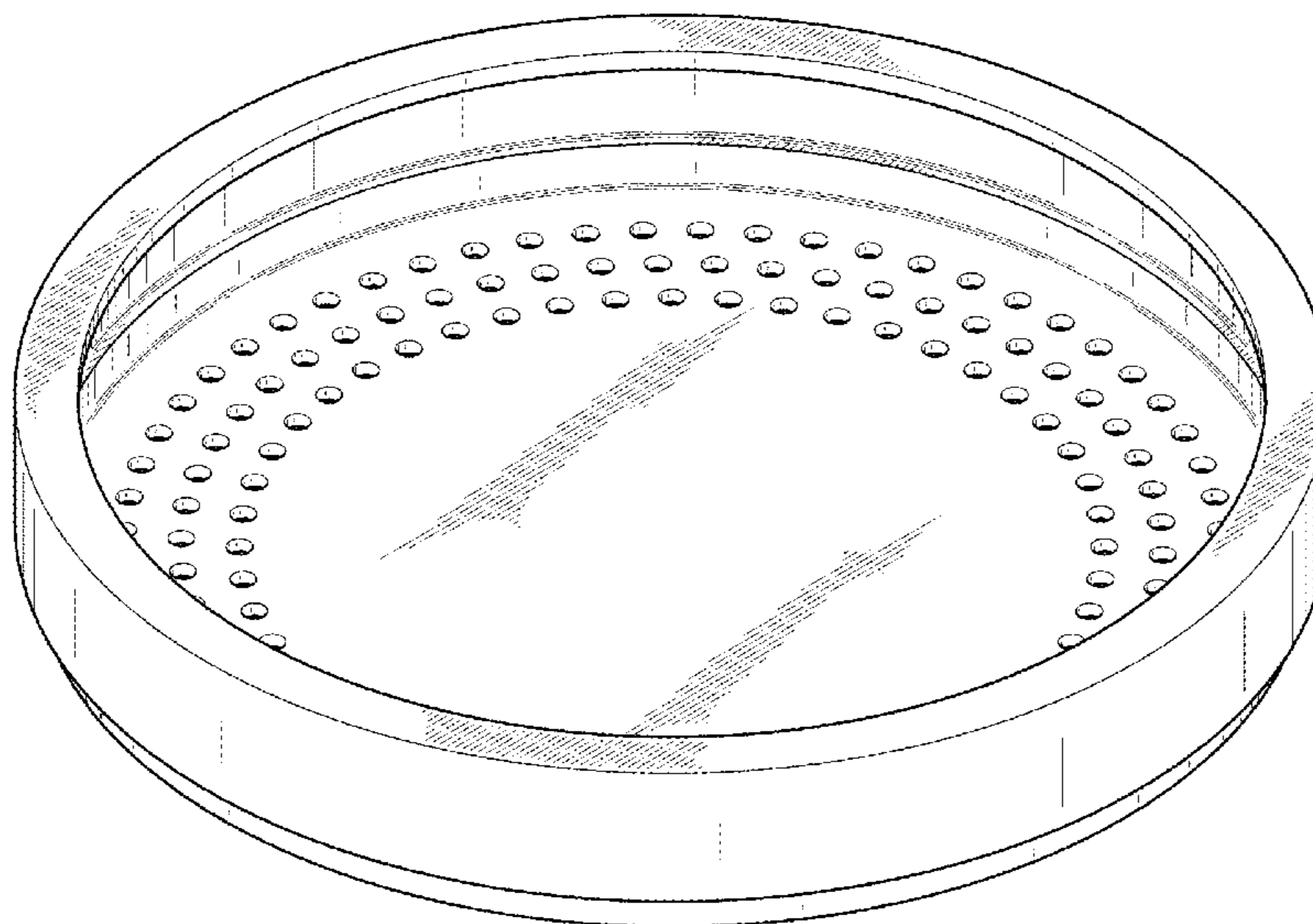
FIG. 7 is a rear elevational view thereof;

FIG. 8 is a cross-sectional view taken along line 8-8 of FIG. 2; and,

FIG. 9 is an enlarged view of the portion shown in box 9 in FIG. 8.

The broken lines shown in FIGS. 8 and 9 represent the boundary of enlarged view and form no part of the claimed design.

1 Claim, 5 Drawing Sheets



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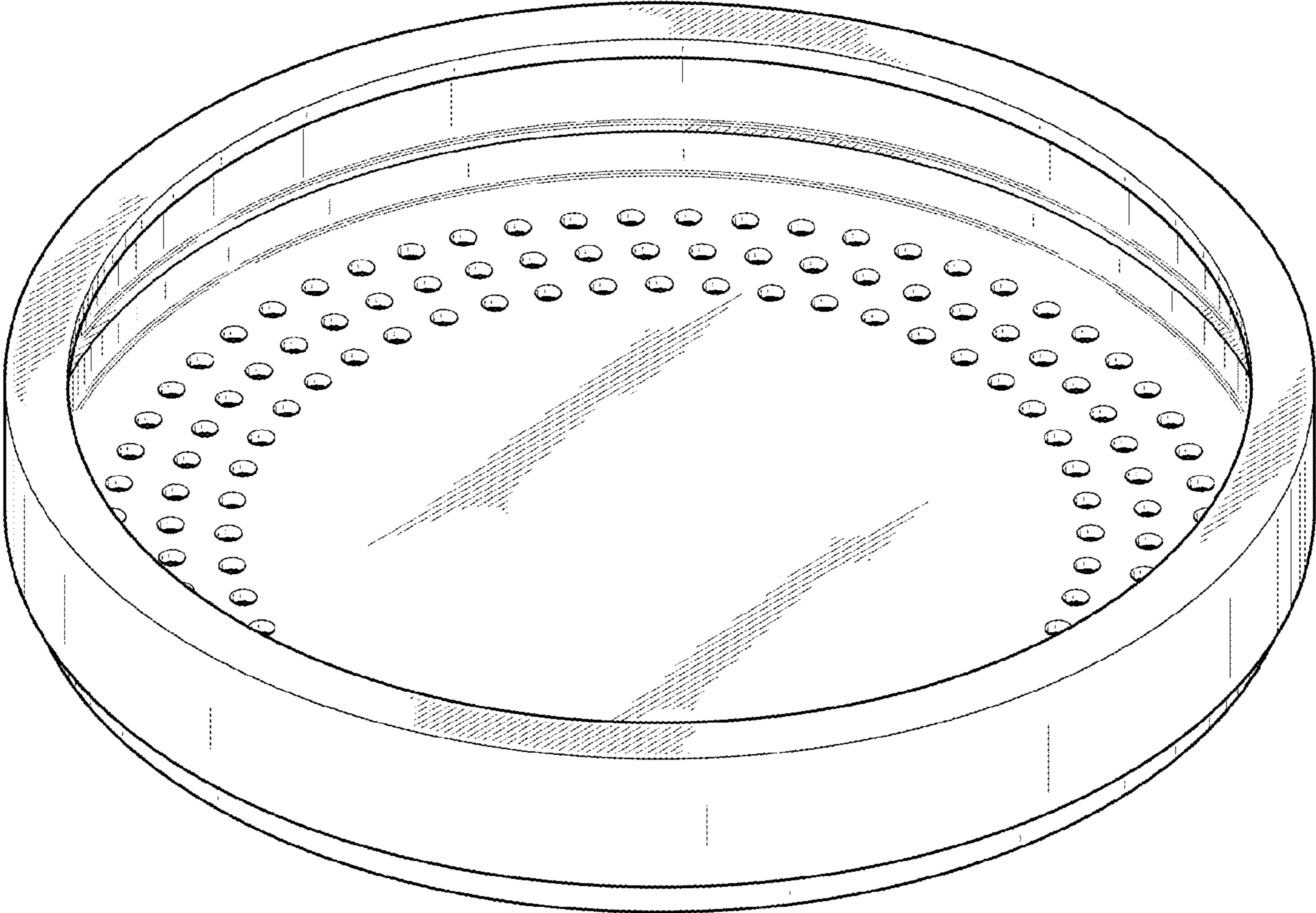


FIG. 1

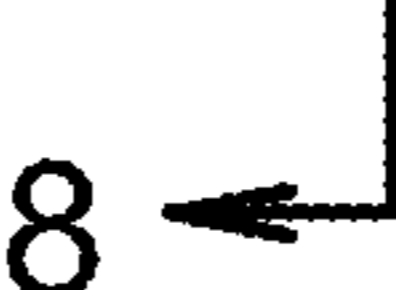
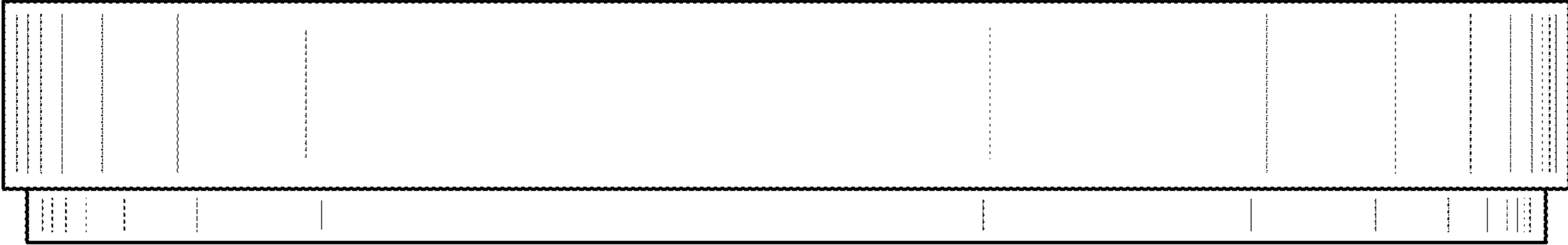
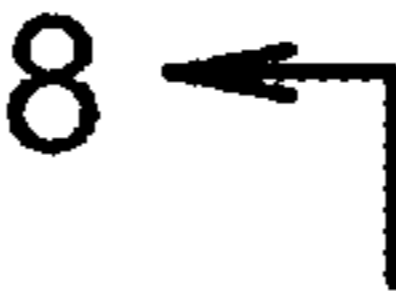


FIG. 2

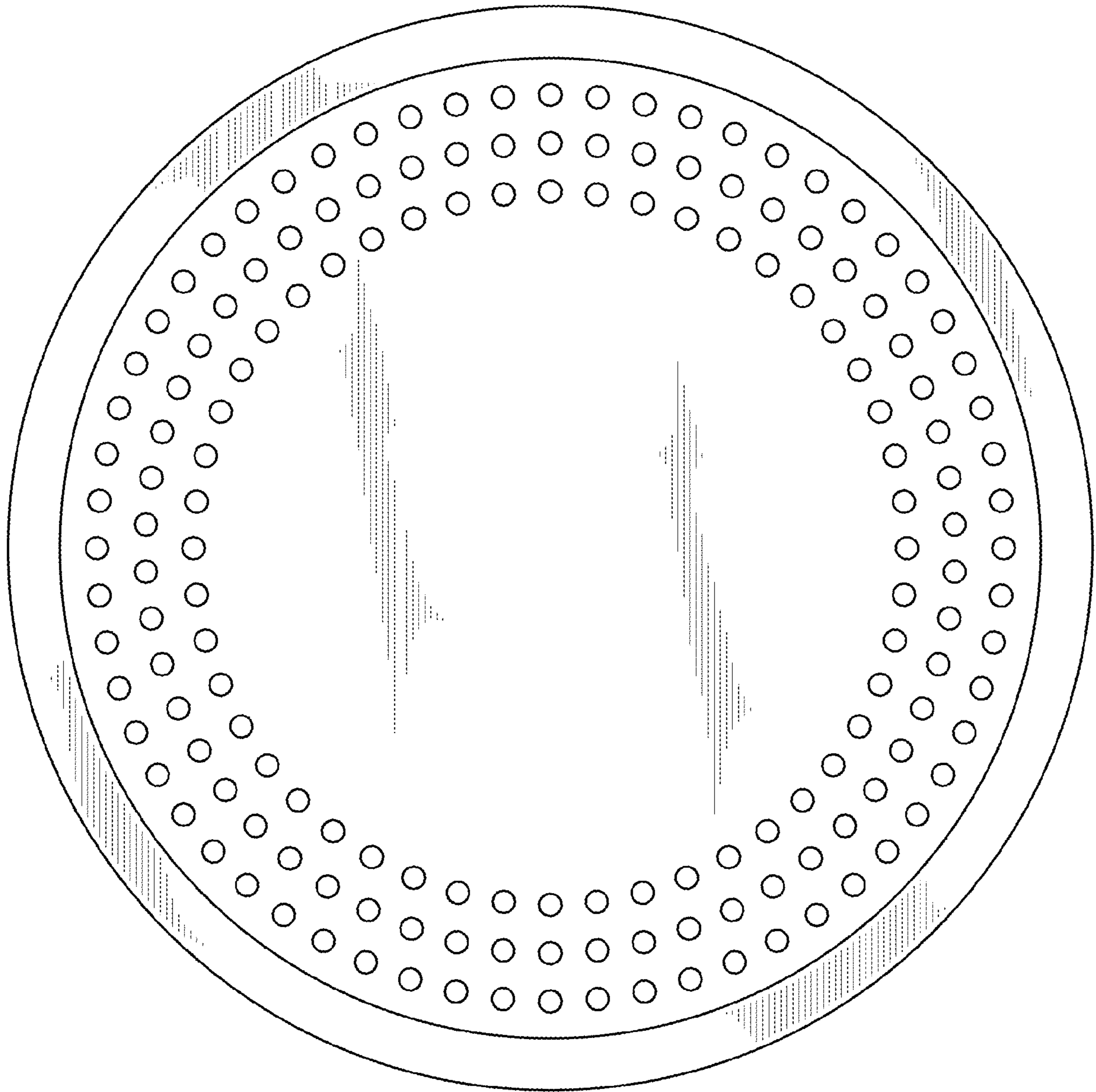


FIG. 3

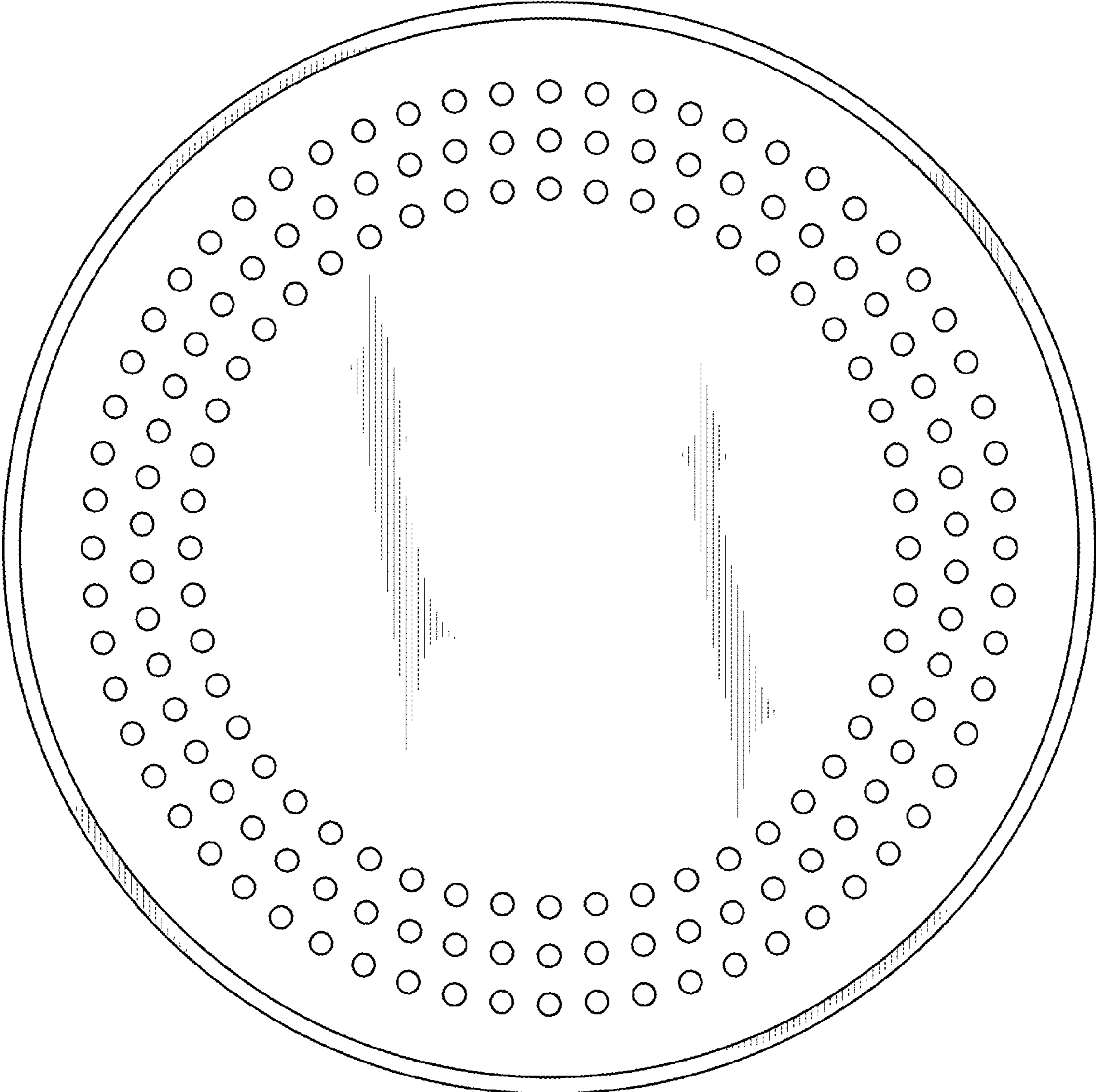


FIG. 4

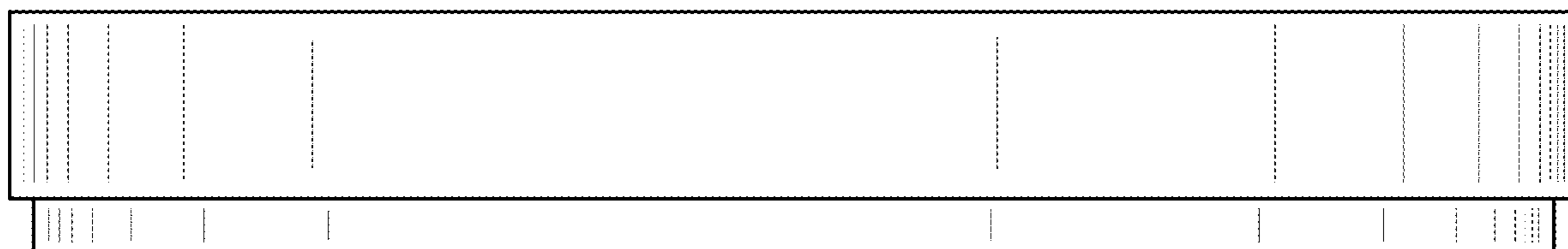


FIG. 5

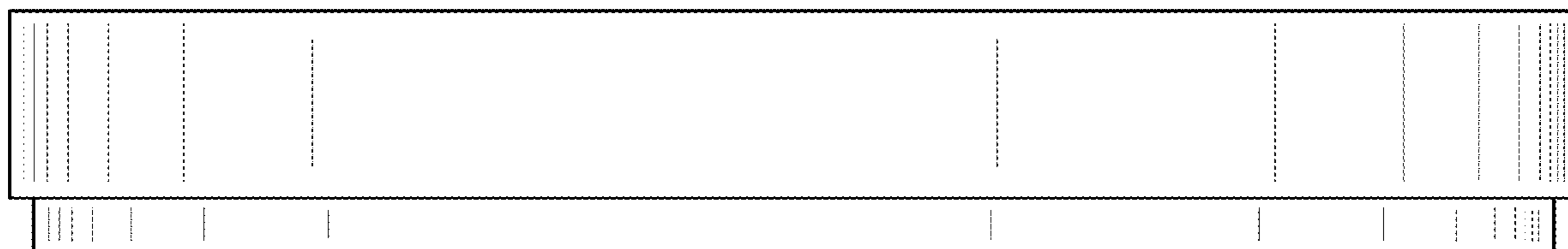


FIG. 6

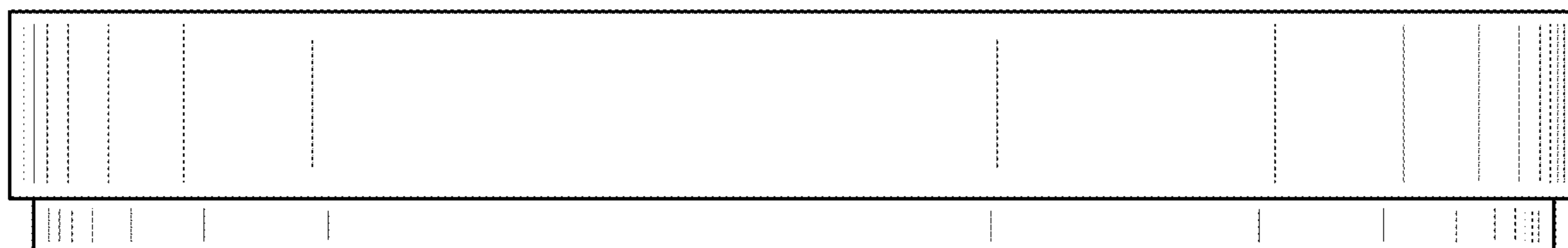


FIG. 7

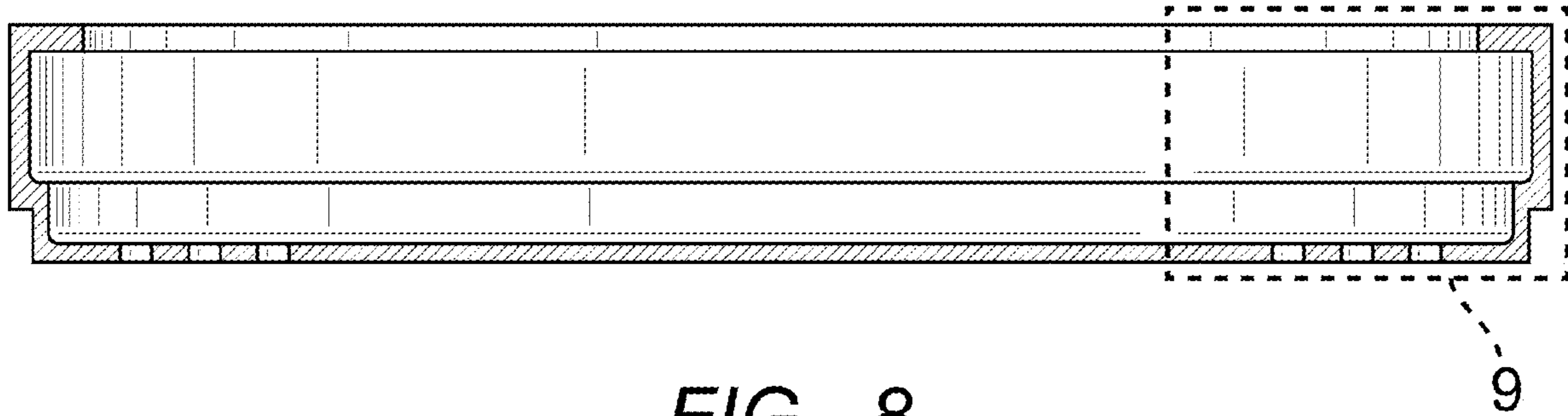


FIG. 8

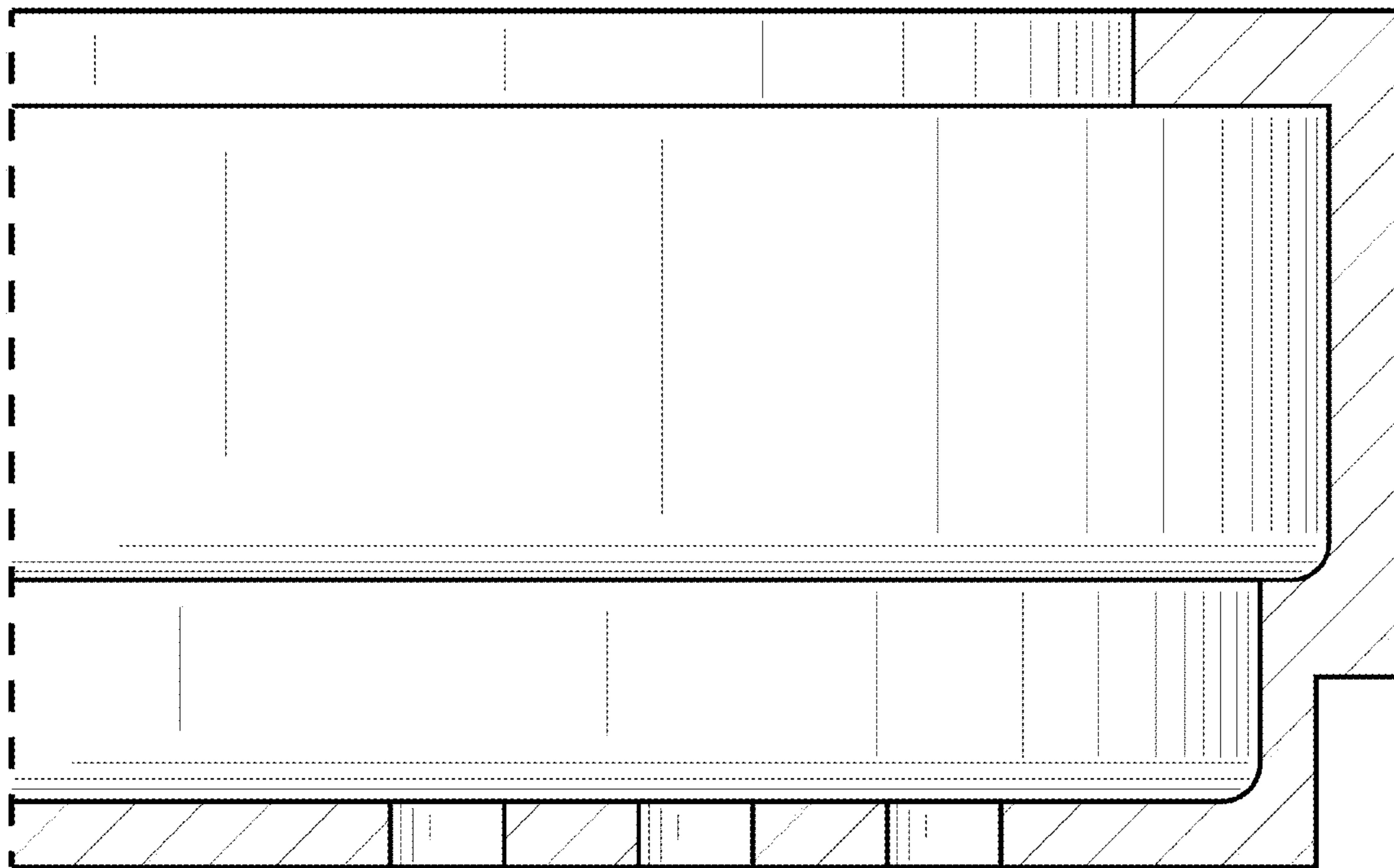


FIG. 9